

Materials List for:

Demonstration of Equal-Intensity Beam Generation by Dielectric Metasurfaces

Gwanho Yoon¹, Dasol Lee¹, Junsuk Rho^{1,2,3}

¹Department of Mechanical Engineering, Pohang University of Science and Technology (POSTECH)

²Department of Chemical Engineering, Pohang University of Science and Technology (POSTECH)

³National Institute of Nanomaterials Technology (NINT)

Correspondence to: Junsuk Rho at jsrho@postech.ac.kr

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Materials

Name	Company	Catalog Number	Comments
Plasma enhanced chemical vapor deposition	BMR Technology	HiDep-SC	
Electron beam lithography	Elionix	ELS-7800	
E-beam evaporation system	Korea Vacuum Tech	KVE-E4000	
Inductively-coupled plasma reactive ion etching	DMS	-	
Ultrasonic cleaner	Honda	W-113	
E-beam resist	MICROCHEM	495 PMMA A2	
Resist developer	MICROCHEM	MIBK:IPA=1:3	
Conducting polymer	Showa denko	E-spacer	
Chromium etchant	KMG	CR-7	
Acetone	J.T. Baker	925402	
2-propanol	J.T. Baker	909502	
Chromium evaporation source	Kurt J. Lesker	EVMCR35D	
Collimated laser diode module	Thorlabs	CPS-635	wavelength: 635 nm
ND:YAG laser	GAM laser	GAM-2000	wavelength: 532 nm
power meter	Thorlabs	S120VC	
CCD Camera	INFINITY	infinity2-2M	
ND filter	Thorlabs	NCD-50C-4-A	
Linear polarizer	Thorlabs	LPVISA100-MP2	
Lens	Thorlabs	LB1676	
Iris	Thorlabs	ID25	
Circular polarizer	Edmund optics	88-096	
sample holder	Thorlabs	XYFM1	
PECVD software	BMR Technology	HIDEP	